AZ 300T / 400T Photoresist Stripper

The CEPSR Clean Room stores AZ 300T and 400T photoresist strippers. They are located in both the large and small yellow rooms under the fume hood with the solvents. Both of these strippers contain alkaline ingredients that are able to clean wafer surfaces of organic contaminants after plasma etching. In addition, they serve as high speed photo resist removers and work to fully dissolve the resist. AZ 300T and 400T are compatible with wet stripping equipment and are water soluble. AZ 400T is produced and filtered with highly controlled trace metals. Always optimize your parameters for the purpose of your particular device.

**Process**

1) Remove the photoresist strippers from under the fume hood. Prepare two beakers, each filled with the stripper needed for your particular device. Set your hotplate for 80 degrees Centigrade.

2) Immerse your sample in the first beaker and place on the hotplate for 10-30 minutes (it may help at this stage to either sonicate or use a stirring bar while your sample is inside the solution).

3) Remove your sample and place in second beaker for stripping solution under same conditions.

4) Take your wafer out and rinse in DI water thoroughly.

5) Blow dry well with nitrogen gun blasts.

6) Pour any used AZ 300T or 400T stripping solution into its waste container labeled AZ 300T/400T STRIPPER WASTE. Place waste container under fume hood with other waste bottles.

7) Clean up your work station.